



# *Hybridisation Issues for Future Detectors\**

*Vertex 2007, Lake Placid*

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PSI



# *Hybridisation Issues for Future Detectors\**

*\*tracking detectors for SLHC experiments*

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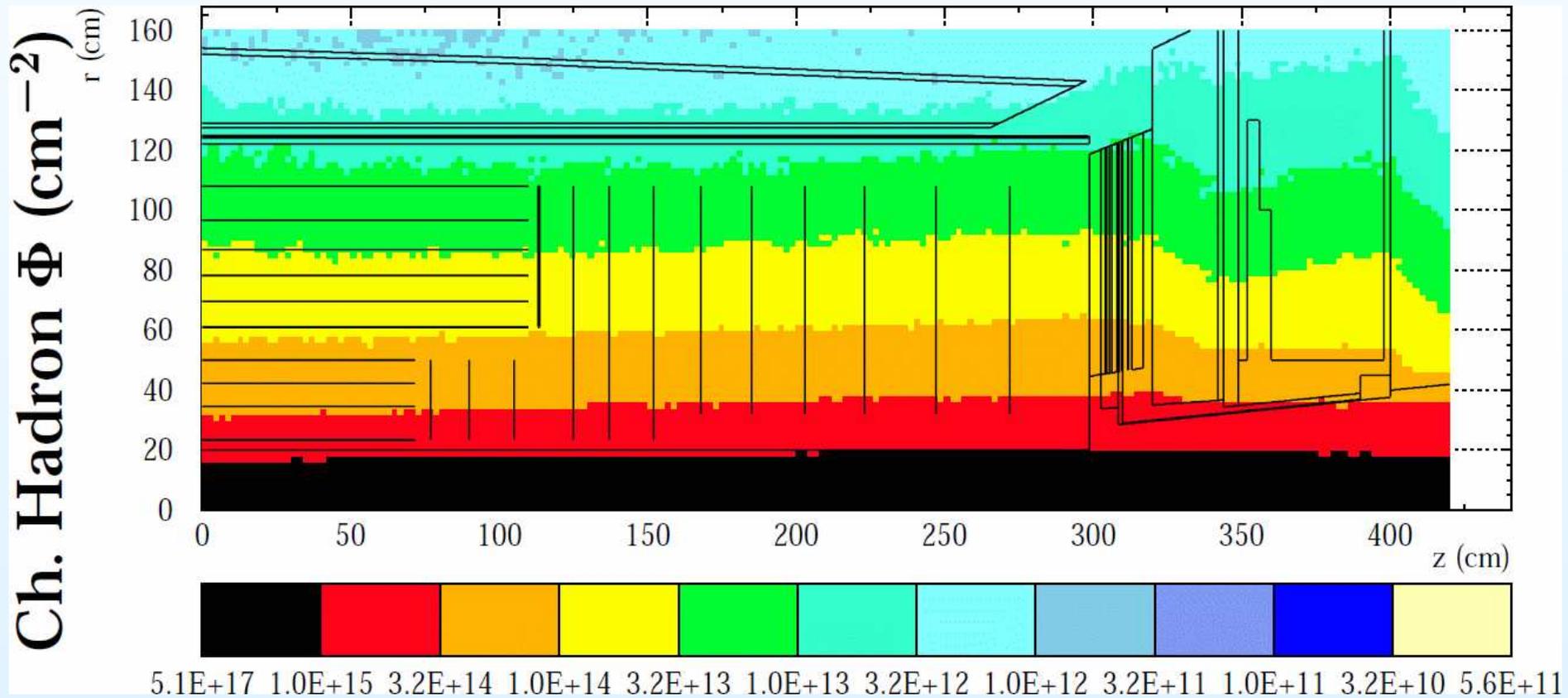
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# Specs of a SLHC Tracking Detector

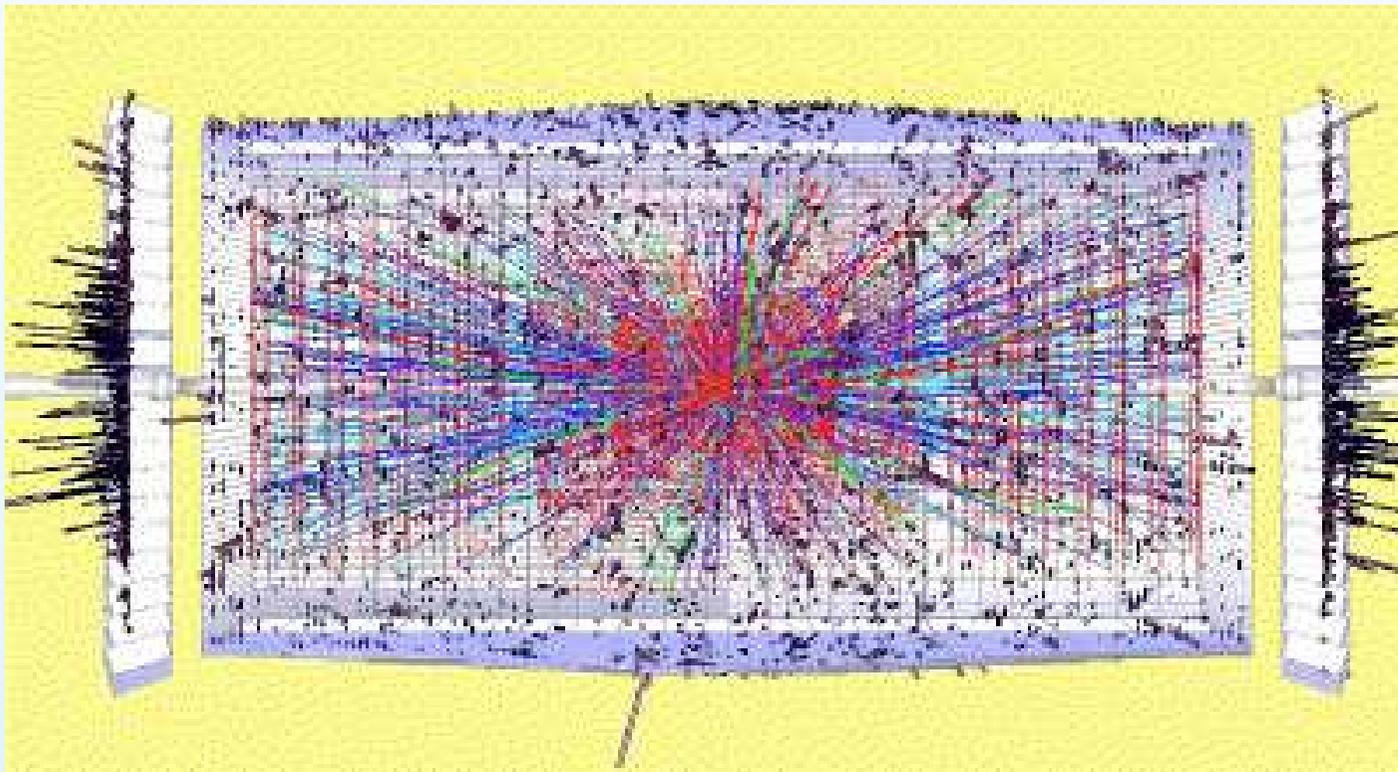
- extrem radiation hard
  - ~10000 tracks/events
  - low mass
- ⇒ low power consumption
- $1.6 \times 10^{16}$  ch.Had./cm<sup>2</sup>
  - ~450 MGy

@4cm



# Specs of a SLHC Tracking Detector

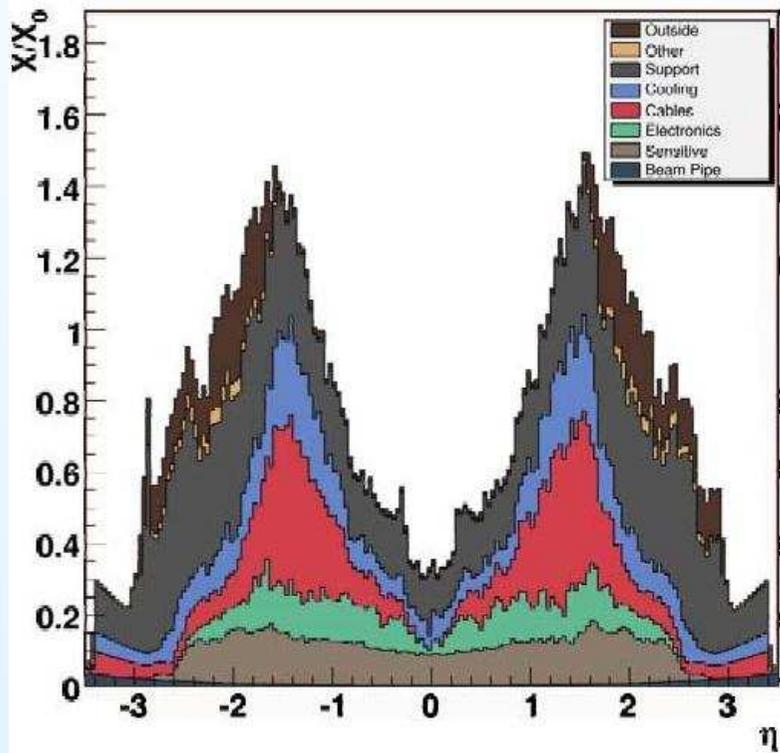
- extrem radiation hard
- $\sim 10000$  tracks/events → high granularity in innermost layers  
relaxes with radius
- low mass  
⇒ low power consumption



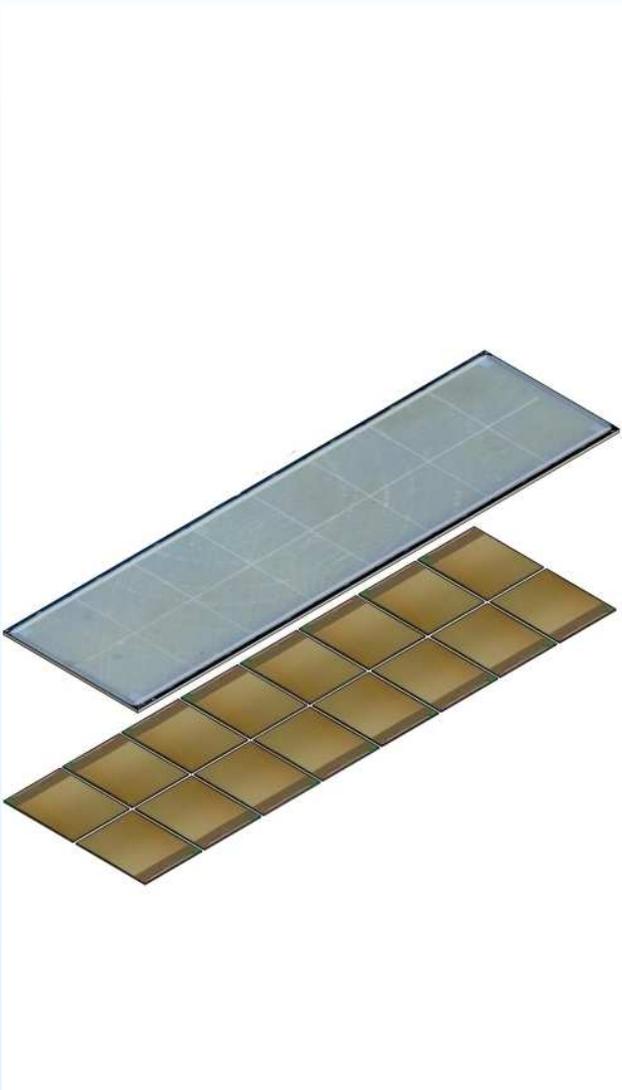
# Specs of a SLHC Tracking Detector

- extrem radiation hard
- ~10000 tracks/events
- low mass  
⇒ low power consumption

...with respect to existing LHC detectors  
contribution of active material not such an issue as @ ILC



# a typical Detector Module - Components



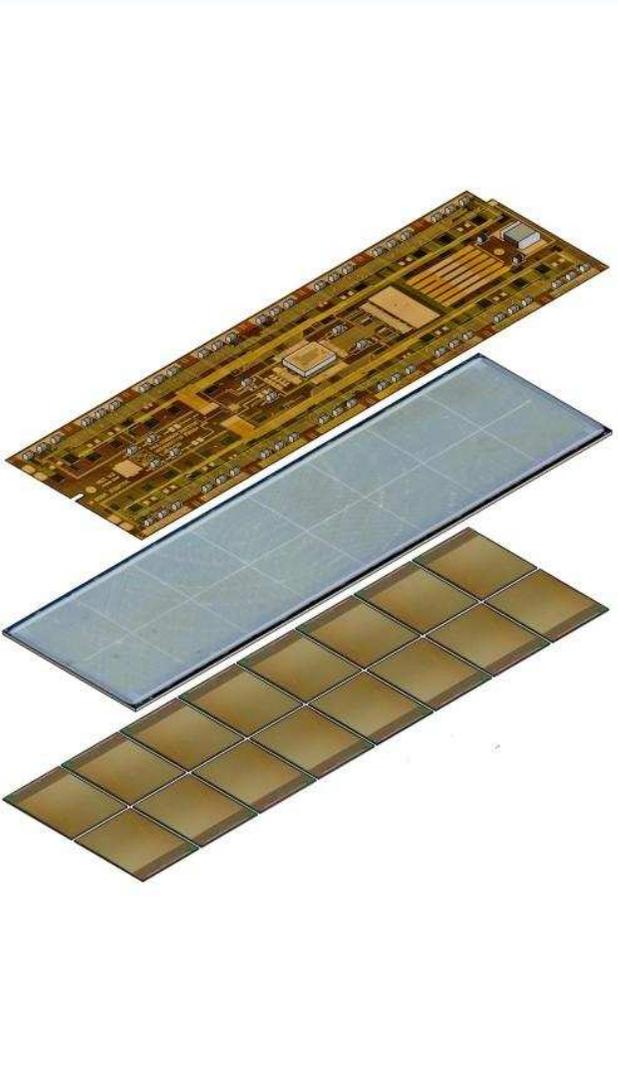
## sensor:

- sensing device
- mostly silicon
- but also diamond
- or even gas as sensitive medium

## ReadOutController:

- amplifier + shaper
- digital logic
- data buffering

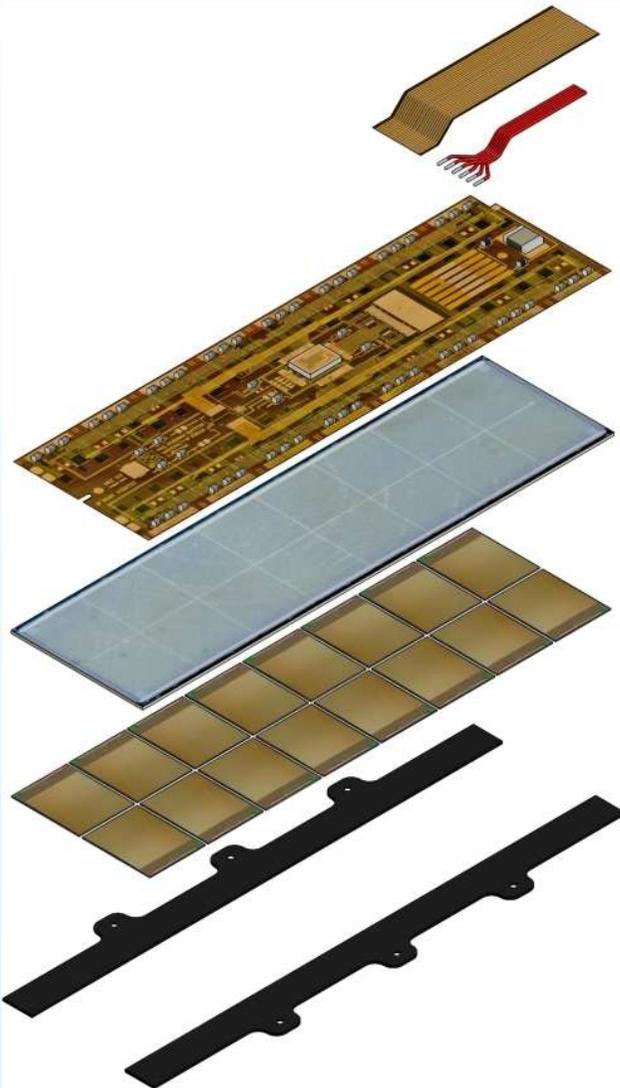
# a typical Detector Module - Components



## Interconnection:

- distributes control + signal from/to chips
- distributes power to chips
- houses additional components:
  - module controller
  - optical transceiver
  - passiv components

# a typical Detector Module - Components



## Cabling

- electrical + optical connection to data acquisition

## Support:

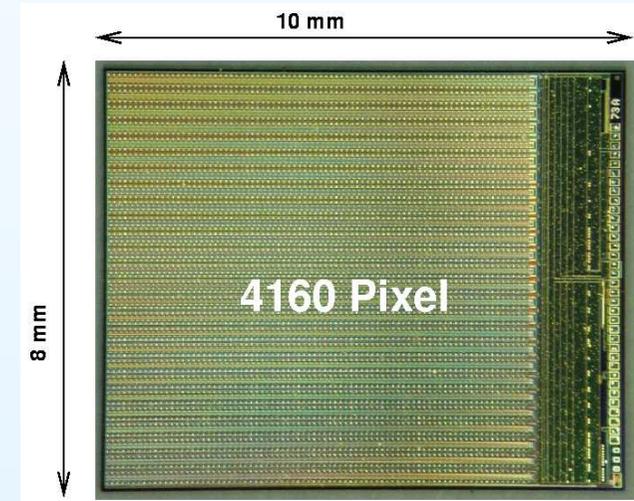
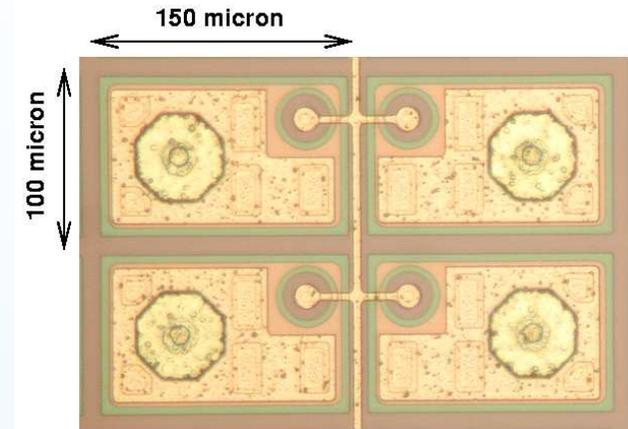
- mechanical fixation to structure
- connection to cooling

# Interconnection: Sensor - ROC

characteristics:

- high number of interconnects  
 $\sim 5-15 \cdot 10^3 / \text{cm}^2$
- low pitch  $\sim 50 \mu\text{m}$
- short distances  $\sim 20 \mu\text{m}$   
(low capacitance)
- moderate resistance  $\sim$  few Ohms

↑ numbers for innermost layers ↑  
...layers at medium radii have bigger pitch



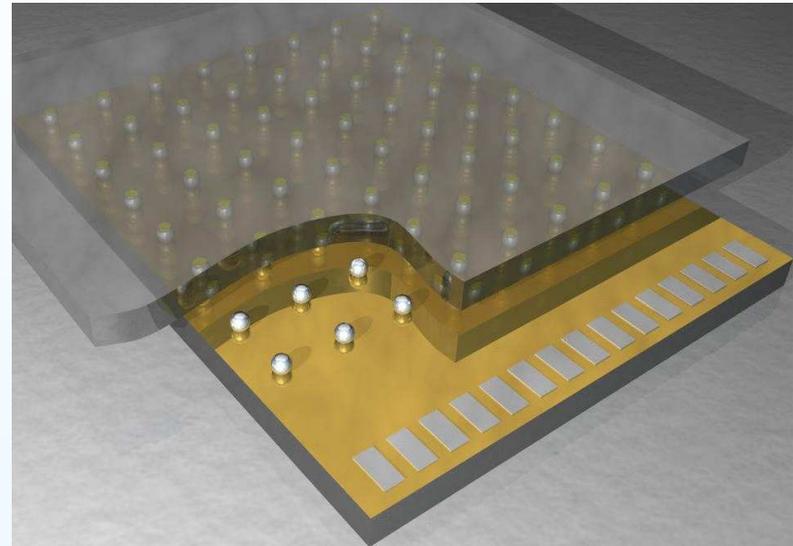
(actual CMS pixel devices)

# Interconnection Technics: Sensor - ROC

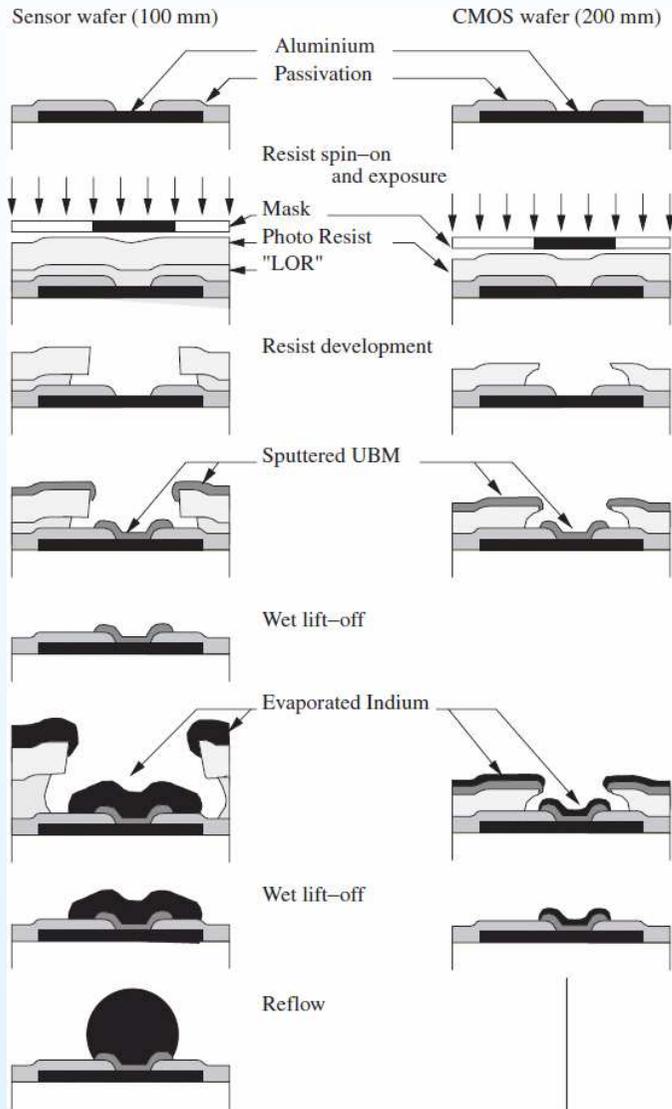
quite a few techniques on the market.

...just a selection:

- bumpbonding
  - fine pitch
    - Indium
    - solder
    - gold
  - low cost
    - C4NP
- SOI direct wafer bonding



# Bumpbonding - Processing

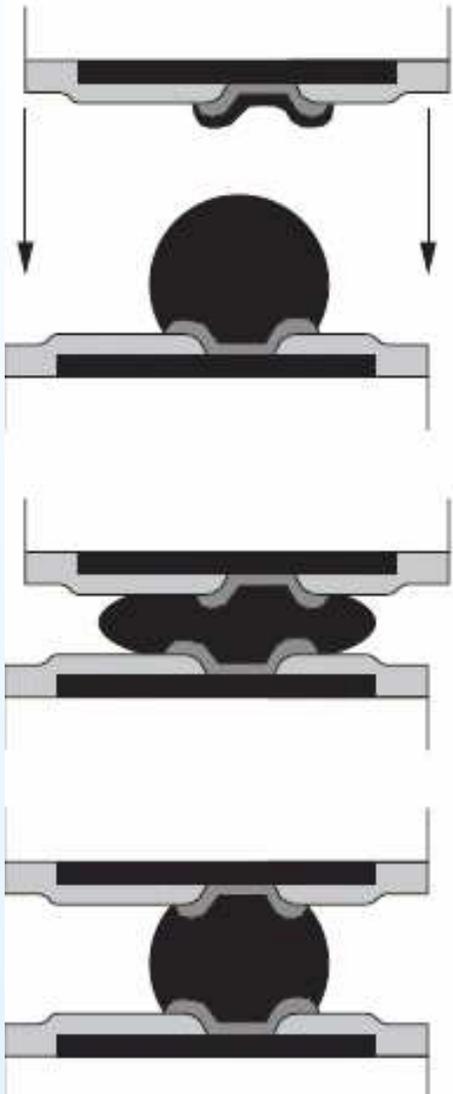


- add UnderBumpMetal\*
  - sputter
  - electroplate
  - evaporate
- add bump material\*
- ( thinning of CMOS )

\*step requires (several) photolithographic steps

CMS Pixel Indium process

# Bumpbonding - Flip-Chip

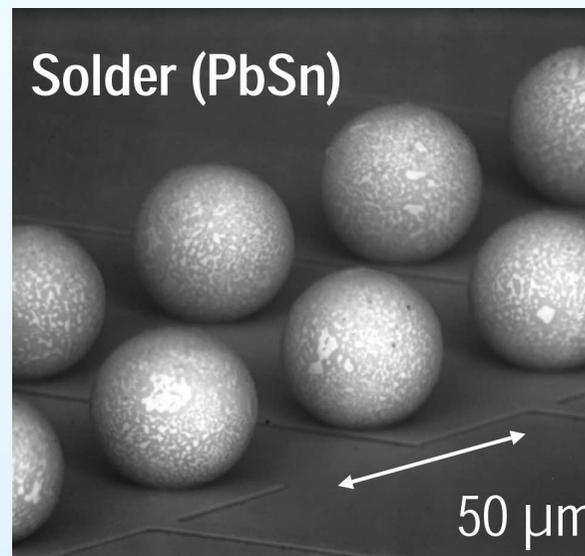
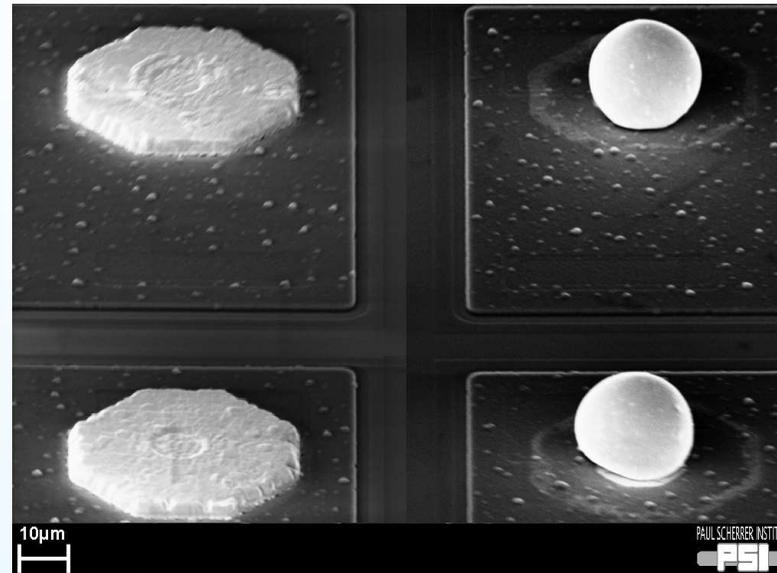
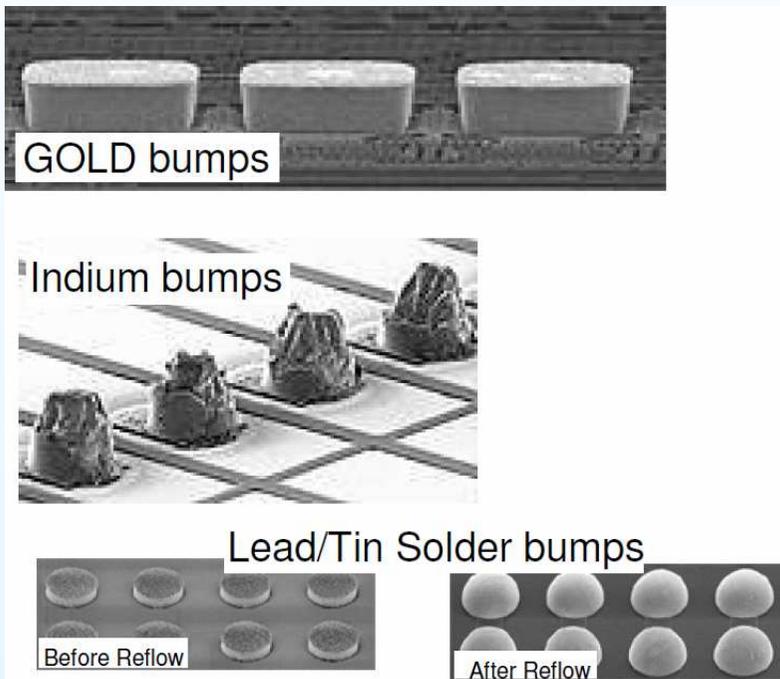


- reflow\*
  - heat
  - special atmosphere
- flip-chip
  - pressure
  - (heat)
- 2. reflow\*

\*reflow parameters (or no reflow) highly process dependent

CMS Pixel Indium process

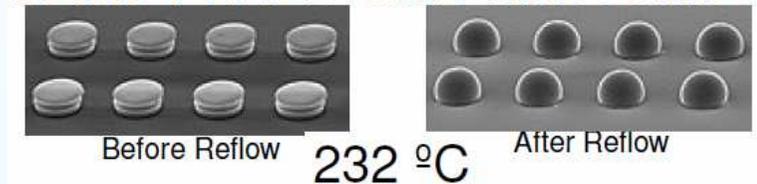
# Bumpbonding - Bumps



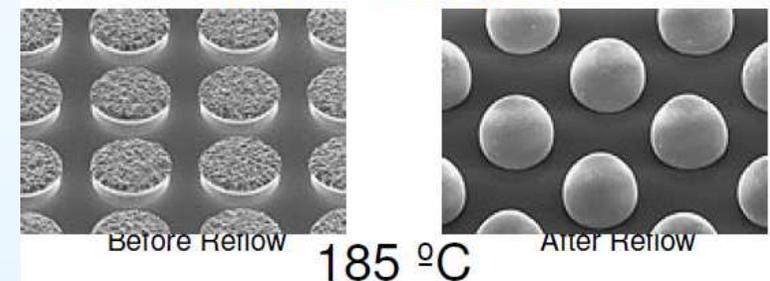
# Bumpbonding - Features

- different technology for connected parts
- low temperature process  $\sim 200\text{C}$   
(even lower without reflow)
- minimum pitch  $\sim 20\ \mu\text{m}$
- use of Known Good Devices (KGD)
- bump yield on good devices  $\sim 99.9\ \%$
- device yield  $\sim 90\ \%$   
when all bugs worked out...
- costly in money ( $300\ \text{CHF}/\text{cm}^2$ ) and time

## LEAD-FREE PURE TIN-BUMPS:

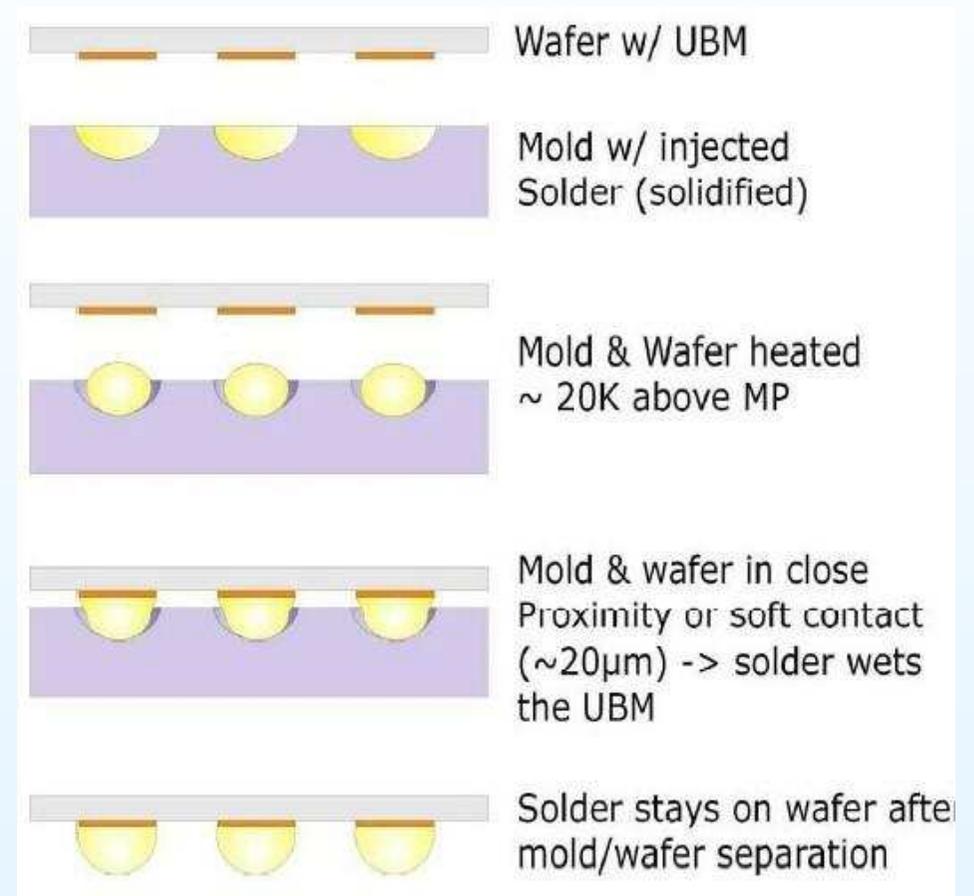
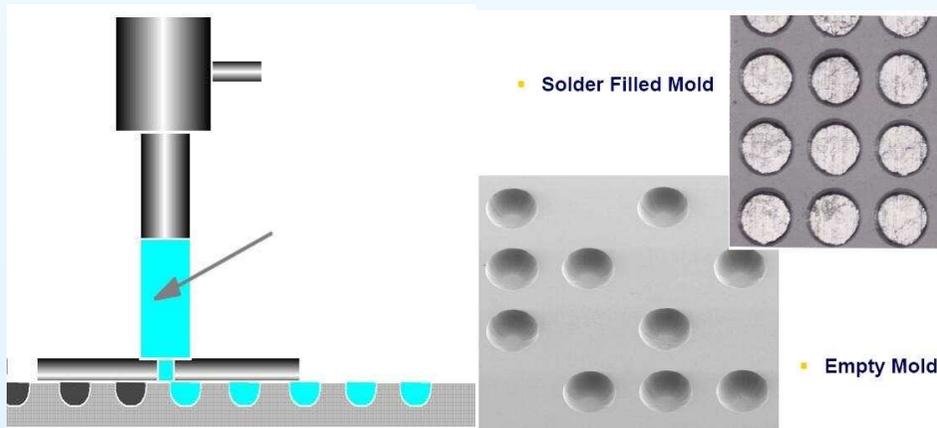


## TIN-BISMUTH



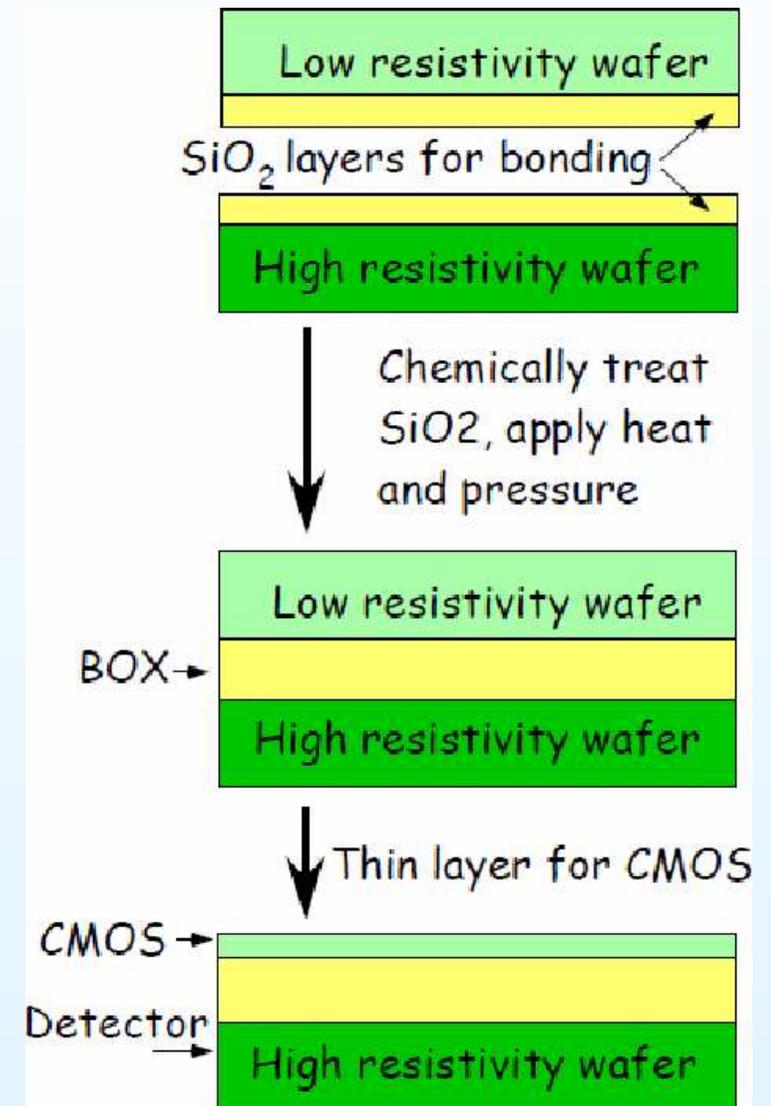
# Bumpbonding - C4NP

- industrial standard
- minimum pitch  
~200micron
- cheap:  
6in wafer ~ 300 CHF



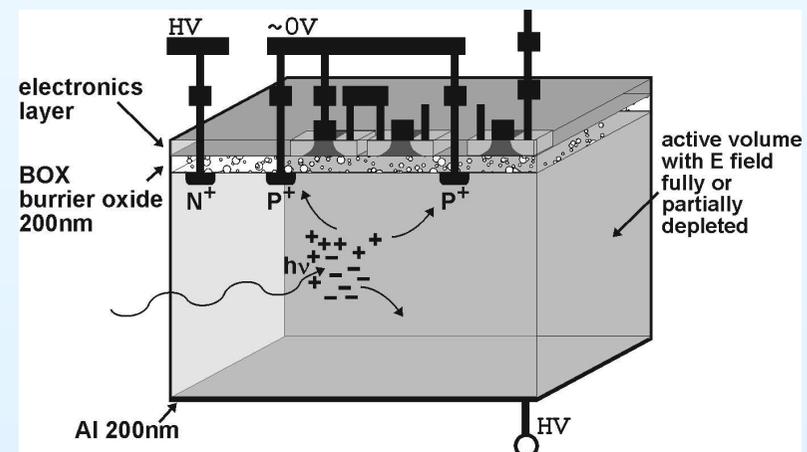
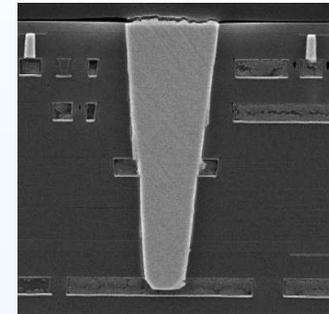
# Silicon Wafer Bonding - Process

- oxide two wafers to be connected
- SiO bonding with:
  - pressure
  - ~500C
- thinning of CMOS part
- processing of both sides
- create vias for interconnection



# Silicon Wafer Bonding - Features

- SOI devices are faster/lower power
- monolithic device
- vias aspect ratio 1 to 8  
⇒ **thinning (few micron) needed** for small viaradius
- quite complex process
- **no complete freedom** of material choice
- Yield: **no KGD possible**



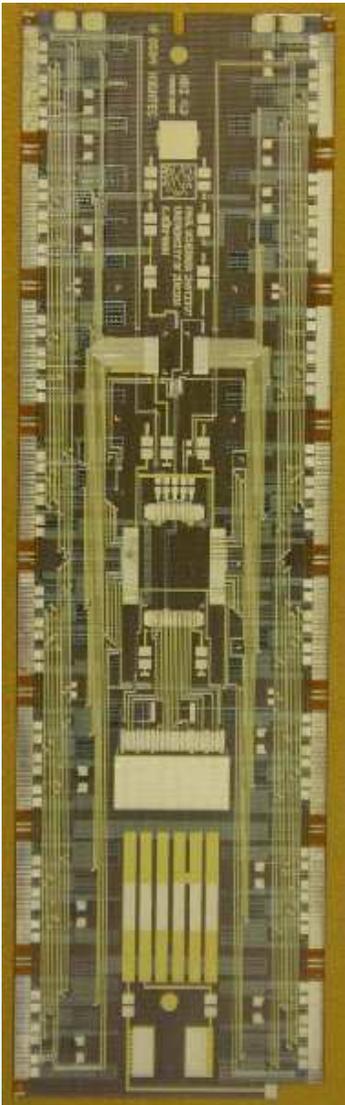
# Interconnection: ROC - Periphery

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some alternatives:

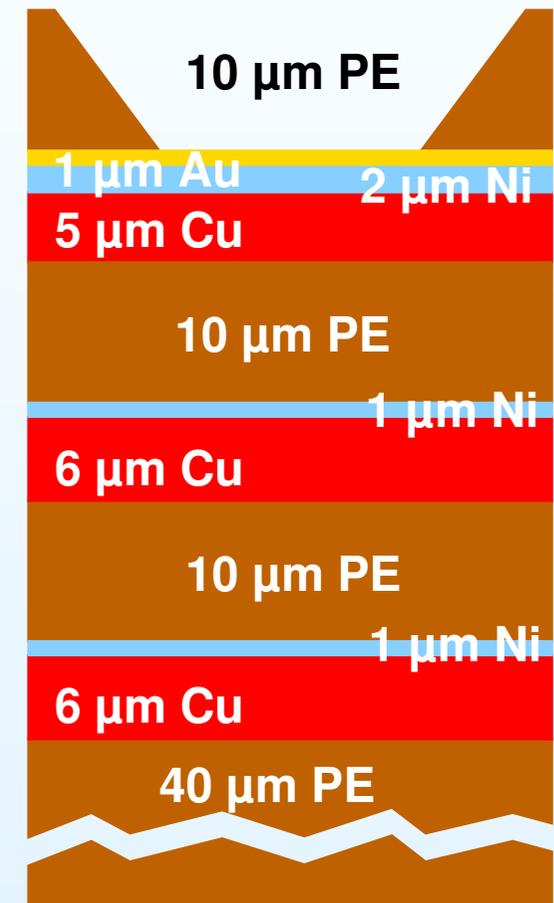
- High Density Interconnect
- MCM-D
- 3D techniques

# Interconnection: HDI



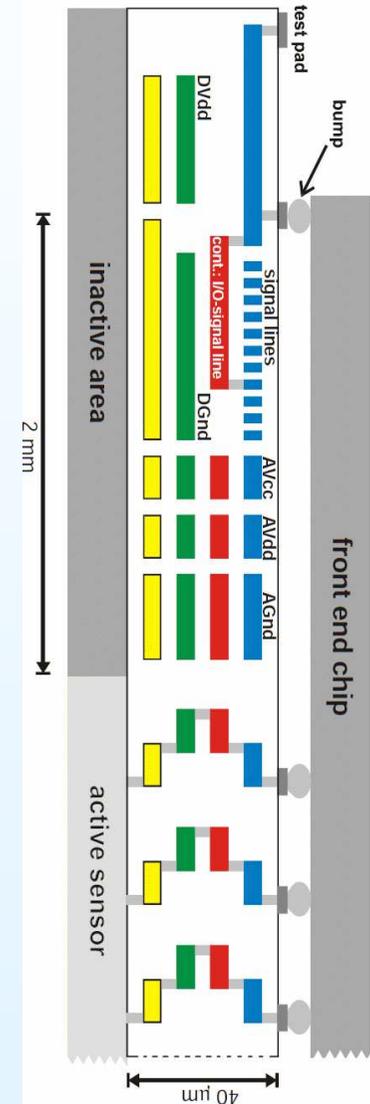
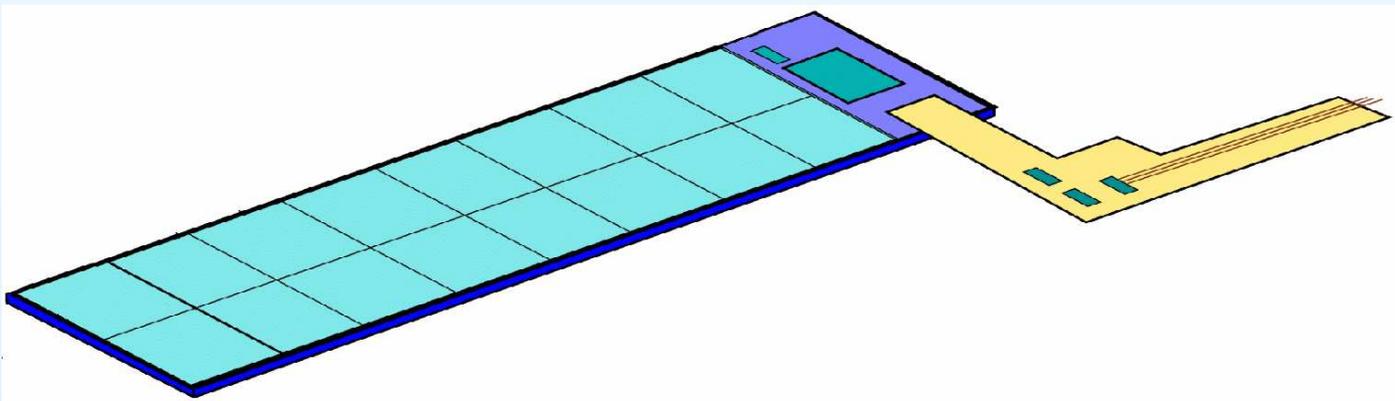
- pitch  $\sim 80 - 150 \mu m$
- yield  $\sim 90 \%$  (bugfixed)
- easy integration additional components:
  - module controller chip
  - optical transceiver
  - passive components
- aluminum instead of copper done (but not standard)
- affordable: 30 CHF/cm<sup>2</sup>

## Layers:



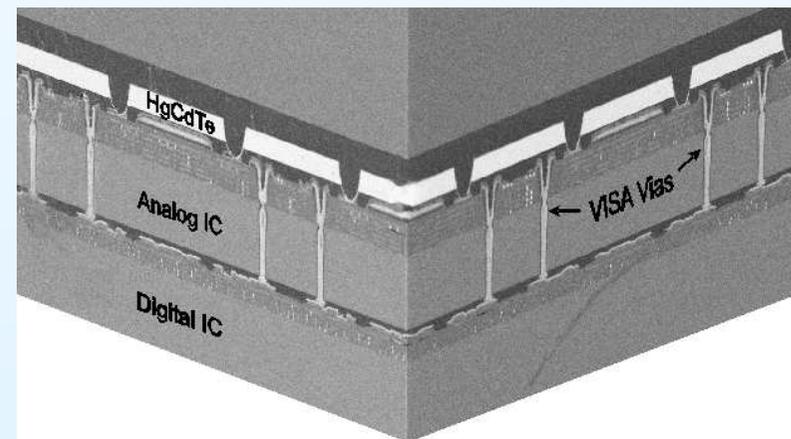
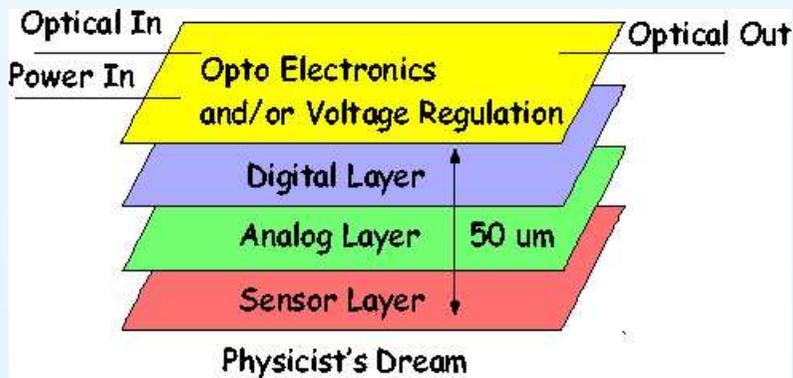
# Interconnection: MCM-D

- additional metal layers on sensor
- only bumpbonding for ROC connection
- additional components on bigger sensor
  - ROC pitch < sensor pitch
  - routing with metall layers
  - choose optimum sensor geometry
- no degradation in sensor performance
- additional processing steps on wafer level



# Interconnection: 3D

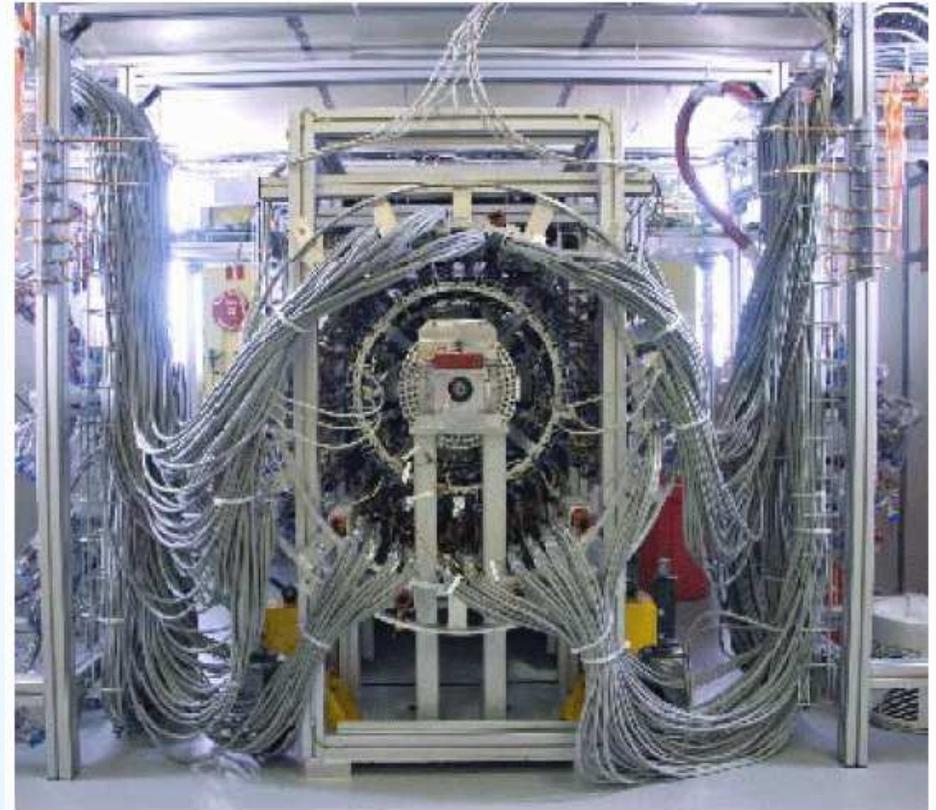
- reduced interconnect length
- connection after processing (bumpbonding)
- mixing of different technologies possible
- thinning needed to reduce via size
- easily integrate module controller in one layer
- additional components on top or separate hybrid



# Interconnection: Power Distribution

## Task:

- power  $O(10.000)$  devices
- with  $O(1 \text{ A}) @ O(1 \text{ V})$
- over a distance  $O(100 \text{ m})$
- one+ (higher) analog voltages/device @ lower currents



# hybridisation on powering level

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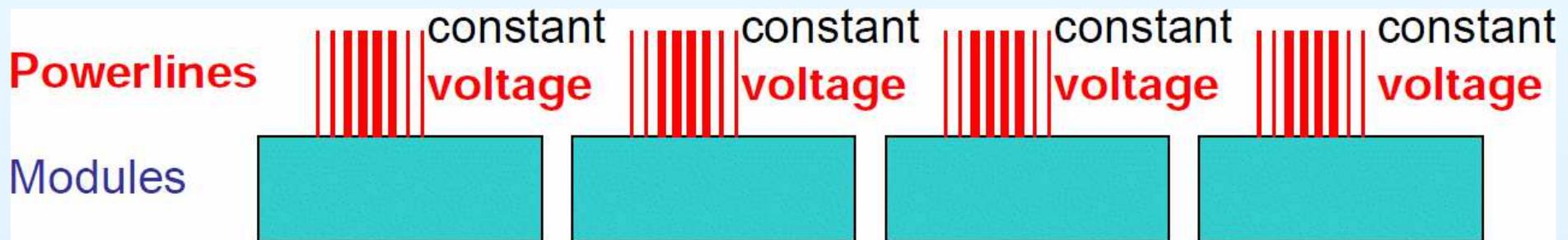
several techniques on the market:

- parallel powering
- DC/DC converters
- serial powering

# Parallel Powering

connect each Module individually :

- easy tuning for each module
- low supply voltage = high voltage drop along powerline
- huge number of powerlines (one per voltage + GND) or linear regulators on frontend
- easy DC connection of control and signal
- highly fault tolerant: one bad module does not effect the others

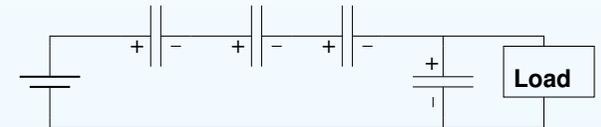


# DC/DC Converters

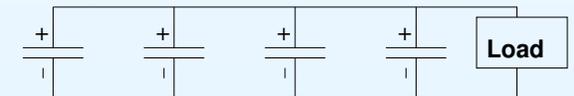
high supply voltage ( $= n * V_{\text{single Device}}$ ) converted on frontend:

- constant voltage source
- one bad module only affects itself
- reduction in ohmic power loss in cables  $\sim \frac{1}{n^2}$
- DC coupling of signal and control
- linear regulators for analog voltages
- needs external capacitance for high efficiency
- DC/DC converter efficiency  $\sim 60 - 80 \%$

## Charge



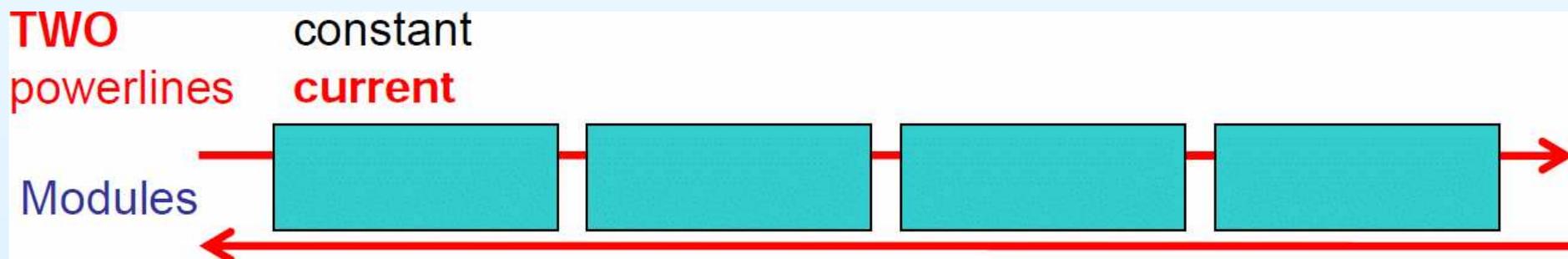
## Discharge



# Serial Powering

connect n Modules in a chain :

- constant current source
- shunt regulator on device
- linear regulator(s) for other voltages (analog)
- AC or opto-coupling of signal and control
- reduces ohmic power loss in cables by  $\frac{1}{n^2}$
- reduces number of cables (connectors) by  $\frac{1}{n}$
- one bad module can result in loss of whole chain
- shunt controller efficiency ~ 60 - 80 %



# Summary

demands on future SLHC tracking detectors are tough:

- very radiation hard
- high granularity
- low material = low power

special interconnections needed on different levels of hybridisation:

- sensor to frontend(s)
- frontends to module/DAQ
- module to services

for all tasks several possible solutions exist:

- from more conventional (f.e. parallel powering)
- up to more fancy ones like 3D frontends or monolithic devices

# Outlook

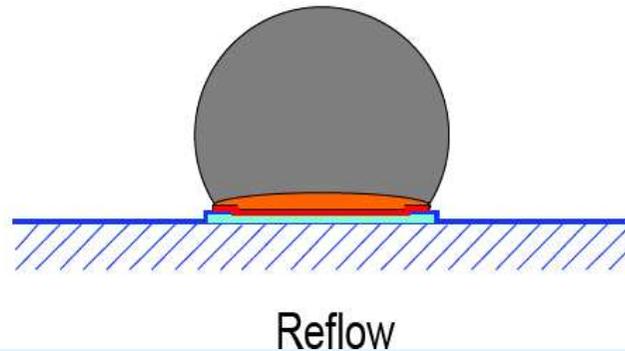
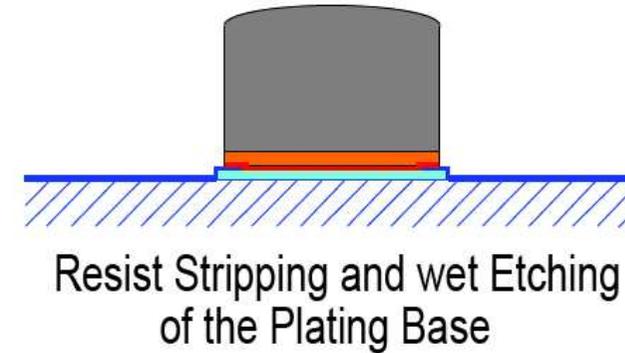
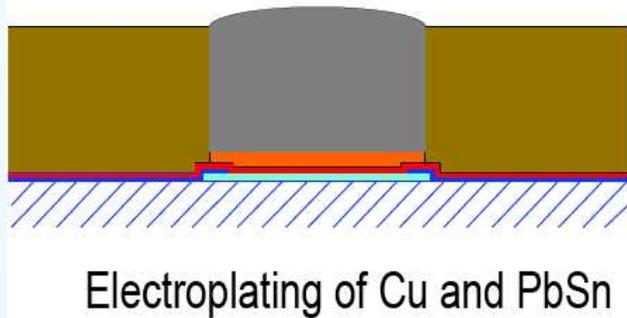
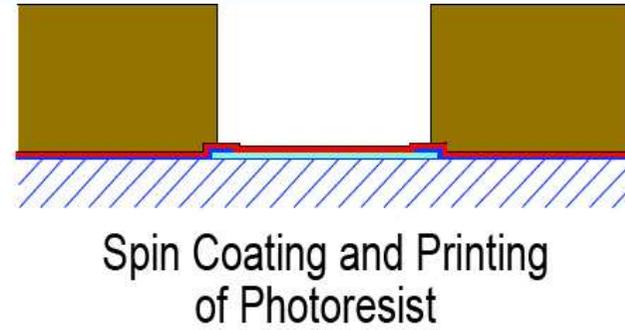
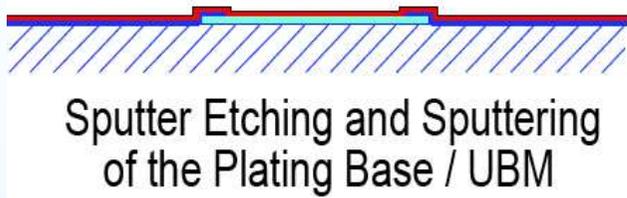
which one to choose?

depends on :

- ability to meet requirements
  - granularity
  - radiation hardness
  - power/material reduction
- confidence in matureness
- cost

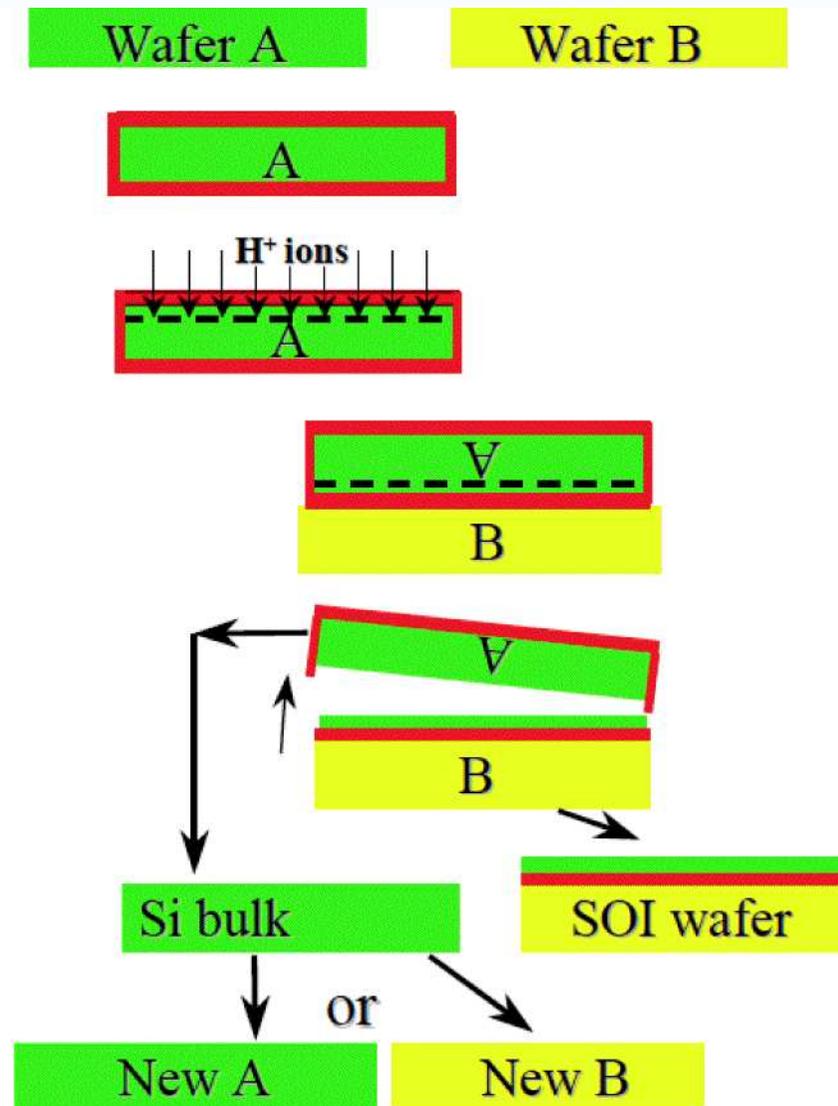
interesting and important development in years to come - stay tuned !

# Backup - electroplated PbSn

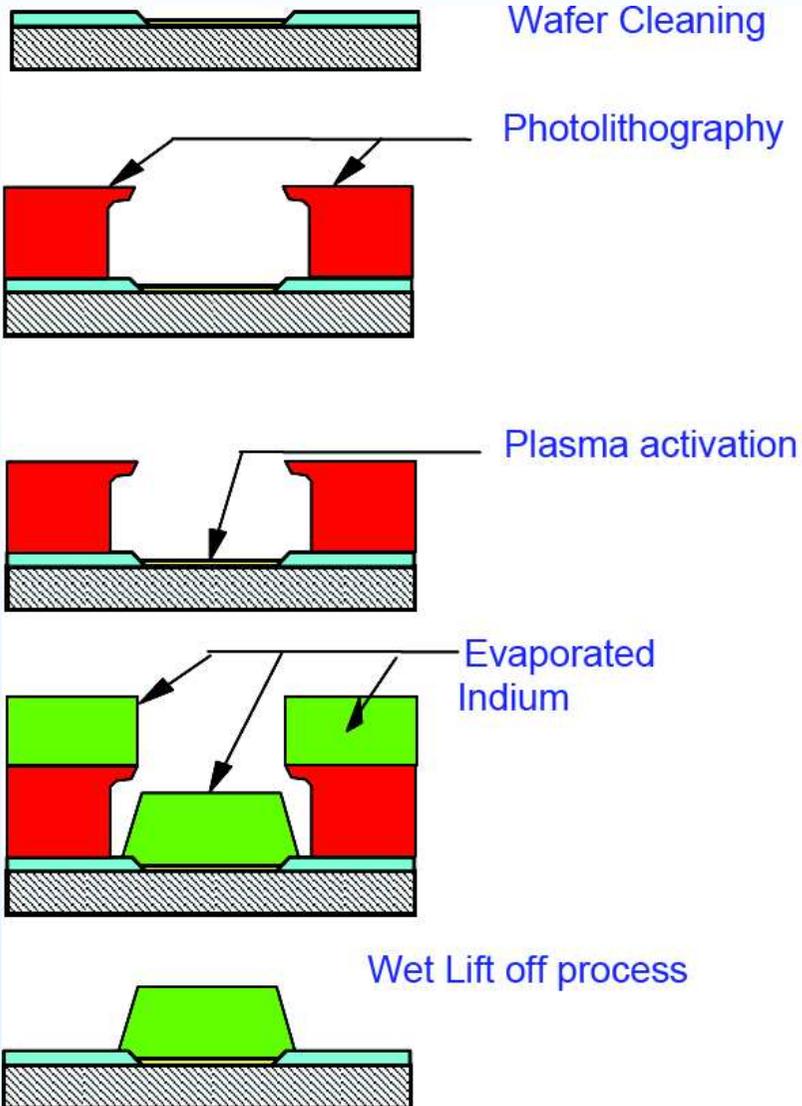


# OKI SOI

- 1 Initial silicon wafers A & B
- 2 Oxidation of wafer A to create insulating layer
- 3 Smart Cut ion implantation induces formation of an in-depth weakened layer
- 4 Cleaning & bonding wafer A to the handle substrate, wafer B
- 5 Smart Cut - cleavage at the mean ion penetration depth splits off wafer A
- 6 Wafer B undergoes annealing, CMP and touch polish => SOI wafer complete
- 8 Split-off wafer A is recycled, becoming the new wafer A or B



# AMS Indium no reflow



## Process parameters:

- Resist Thickness: 15  $\mu\text{m}$
- Pre-bake: 30min @ 80  $^{\circ}\text{C}$
- Deposition rate: 0.5  $\mu\text{m}/\text{min}$
- Dep. Pressure:  $9 \times 10^{-7}$  Torr
- Temp. during Dep. < 50  $^{\circ}\text{C}$